

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

**Examiner: S.D. ROSASCO; Art Unit: 1756; Docket No.: 2695**

**In RE: Application of Jochen ALKEMPER, et al**

**Ser. No.: 10/628,059**

**Filing Date: July 25, 2003**

May 18, 2006

ATT: EXAMINER S.D. ROSASCO

Herewith is the missing page 6.

Respectfully,

Michael J. Striker

A large, stylized handwritten signature in black ink, starting from the bottom left and curving upwards and to the right, ending near the name "Michael J. Striker".

expansion of at most 0.5 ppm/°C, said covering layer comprising at least one individual layer and said reflective layer adhering to the covering layer.

36.(new) The element as defined in claim 35, wherein the reflective layer is a multilayer coating consisting of alternating layers of Mo and Si.

37.(new) The element as defined in claim 35, consisting of a mirror for extreme ultraviolet microlithography.

38.(new) The element as defined in claim 35, consisting of a mask or mask blank for extreme ultraviolet microlithography.

39.(new) The element as defined in claim 35, further comprising an absorbing layer, provided on the reflective layer.

40.(new) The element as defined in claim 35, wherein said covering layer comprises silicon dioxide and at least one dopant comprising at least one other metal oxide, F or a mixture thereof.

41.(new) The element as defined in claim 40, wherein said at least one dopant is  $\text{TiO}_2$  and said  $\text{TiO}_2$  is included in said covering layer in an amount such that said coefficient of thermal expansion of said covering layer matches said coefficient of thermal expansion of said base layer.